Supplementary Information



Figure S1. ¹H NMR of poly(glycidyl methacrylate) obtained by RAFT polymerization.



Figure S2. SEC trace of poly(glycidyl methacrylate) obtained by RAFT

polymerization.



Figure S3. Neutron reflectivity profile of native silicon oxide after plasma etching. The open circles are the measured reflectivity and the continuous line is the calculated reflectivity based on the model shown in the inset graph ($h_{\text{SiO2}} = 0.9 \text{ nm}$, $\Delta h_{\text{SiO2}} = 0.3 \text{ nm}$ and $SLD_{\text{SiO2}} = 3.3 \times 10^{-6} \text{ Å}^{-2}$).



Figure S4. SPM height (left), phase (middle) and 3D (right) images of the surface of poly(glycidyl methacrylate) pseudo-brushes.